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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

REFERENCES FOR CONSIDERATION BY EXAMINER

Atty. Docket No. (Opt.)

005434

Applicant
Shang, et al.


Application Number
09/741,529

Filed
December 19, 2000

For: **On-Site Cleaning Gas Generation for Process Chamber Cleaning**

Certification Under 37 C.F.R. § 1.10

I hereby certify that this document is being deposited with the United States Postal Service as **Express Mail No. EV351127834US** to Addressee in an envelope addressed to: Mail Stop Issue Fee, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on **November 7, 2003**.


Carolyn J. Williams

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The Commissioner is requested to consider the references submitted concurrently herewith before issuing the U.S. Application No. 09/741,529 (the "Application") as a patent. The request is being sent in the public interest on behalf of our client, who shall remain anonymous. We do not represent any of the applicants or the assignee of the Application.

The submitted references are material to the claims of the Application as published in U.S. Patent Application Publication No. 2002/0074013. Of those references, EP 0 819 780 includes many of the details of the systems described and claimed in the Application. Note that Applied Materials, Inc. is assignee of this Application and the applicant of the European patent application. WO 99/28538 includes details regarding the electrolysis of HF to form F₂. A nexus to combine those two references may be found in the International Sematech report, which notes that emissions from a chamber cleaning process include HF and F₂, among other gases. Therefore, the International Sematech report teaches that HF and F₂ ("feed gas" and "cleaning gas," respectively, as claimed in the Application) were present within the chamber during cleaning. Note that each of these three references was published more than a year before the Application was filed, and therefore, the applicants cannot swear behind such references.

-2-

No fees are believed to be due with this paper. However, the Director is hereby authorized to charge any fees due, or refund any credit, to Deposit Account No. 50-0456 of Gray Cary Ware & Freidenrich LLP for any fees.

Respectfully submitted,

Gray Cary Ware & Freidenrich LLP
~~Attorneys for the Requestor~~

Dated: 11/7, 2003

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PTO/SB/08A (04-03)

REFERENCES FOR CONSIDERATION BY EXAMINER				Application Number	09/741,529
				Filing Date	December 19, 2000
				First Named Inventor	Shang, et al.
				Group Art Unit	1746
				Examiner Name	Kornakov, M.
Sheet	1	OF	2	Attorney Docket Number	005434

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Passages or Figures Appear
		Number	Kind Code (if known)			
	A1	4,818,326		04/04/89	Liu et al.	
	A2	5,207,836		05/04/93	Chang	
	A3	5,679,215		10/21/97	Barnes et al.	
	A4	5,693,147		12/02/97	Ward et al.	
	A5	6,544,345	B1	04/08/03	Mayer et al.	

Examiner Initials	Cite No.	FOREIGN PATENT DOCUMENTS		Publication Date MM-DD-YYYY (Number 43)	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Passages or Figures Appear
		Country Code	Number			
	B1	WO 99/28538	A1	06/10/99	Fluoro-Gas Limited	
	B2	EP 0 819 780	A2	01/21/98	Applied Materials, Inc.	
Examiner Signature				Date Considered		



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				Group Art Unit		1746	
				Examiner Name		Kornakov, M.	
Sheet	2	of	2	Atty Docket Number		005434	
Examiner Initials	Cite No.	OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS					Date
	C1	International Sematech, "Motorola Evaluation of the Applied Science and Technology, Inc. (ASTeX) Astron Technology for Perfluorocompound (PFC) Emissions Reductions on the Applied Materials DxL Chemical Vapor Deposition (CVD) Chamber."					April 16, 1999
	C2	Astron, "Reactive Gas Generators," MKS Instruments, Inc., 4 pages.					
	C3	Flamm et al., "Reaction of Fluorine Atoms with SiO ₂ ," J. Appl. Phys., 50 (10), pages 6211-3,					October 1980
	C4	Mucha et al., "Chemiluminescent Reaction of SiF ₂ with Fluorine and the Etching of Silicon by Atomic and Molecular Fluorine," (6), Pages 4553-4, J. Appl. Phys., 53(6).					June 1982
Examiner Signature						Date Considered	